L Number	Hits	Search Text	DB	Time stamp
	5	"6251740"	USPAT; US-PGPUB;	2003/04/28
- !	12	("5095346" "5273925" "5381365"	EPO; JPO; IBM_TDB USPAT	2003/04/28
		"5394000" "5434812" "5494854" "5494857" "5739579" "5767541" "5926359" "6025226" "6069051").PN.		16:01
-	0	(capacitor adj sturcture) and leg	USPAT; US-PGPUB; EPO; JPO;	2003/04/28 16:07
-	105	(capacitor adj structure) and leg	IBM_TDB USPAT; US-PGPUB;	2003/04/28
	48	((capacitor adj structure) and leg) and	EPO; JPO; IBM_TDB USPAT;	2003/04/28
		channel	US-PGPUB; EPO; JPO; IBM TDB	16:08
-	2	(((capacitor adj structure) and leg) and channel) and (sidewall adj spacer)	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/04/28 16:10
- į	0	20030067023.URPN.	USPAT	2003/04/28
-	34	(((capacitor adj structure) and leg) and channel) and electrode	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/04/28 16:11
	1	((((capacitor adj structure) and leg) and channel) and electrode) and (bottom adj electrode)		2003/04/28 16:11
- 1	9	((((capacitor adj structure) and leg) and channel) and electrode) and (second adj electrode)	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/04/28
-	25	((((capacitor adj structure) and leg) and channel) and electrode) not (((((capacitor adj structure) and leg) and channel) and electrode) and (second	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/28 16:25
- j	6	adj electrode)) ("4551743" "4740480" "5017981" "5066608" "5223730" "5252517").pn.	USPAT	2003/04/28
-	136		USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/04/28 16:27
	136	(capacitor and (bottom adj electrode) and channel and (sidewall adj spacer)) and (dielectric or insulat\$4)	USPĀT; US-PGPUB; EPO; JPO;	2003/04/28 16:27
	3	((capacitor and (bottom adj electrode) and channel and (sidewall adj spacer)) and (dielectric or insulat§4)) and ((bottom adj electrode) with ((titanium adj nitride) or ("Tin")))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/28
-	7	("4822753" "5045899" "5250467" "5281549" "5332685" "5648291"	USPAT	2003/04/28 16:36
-	7	"5700731").PN. ("4822753" "5045899" "5250467" "5281549" "5332685" "5700731"	USPAT	2003/04/28
- !	36	"5710073"), PN. 5895239.URPN.	USPAT	2003/04/28

F	98	("MIM" adj capacitor) and channel	USPAT:	12003/04/28
			US-PGPUB;	17:04
	1		EPO; JPO;	
: -	3	(("MIM" adj capacitor) and channel) and	IBM_TDB USPAT;	2003/04/28
	1	(sidewall adj spacer)	US-PGPUB;	17:05
1	1		EPO; JPO;	
	1 11	((1),734)	IBM_TDB	
	11	(("MIM" adj capacitor) and channel) and (spacer)	USPĀT; US-PGPUB;	2003/04/28
	i	(apassa)	EPO; JPO;	1
			IBM_TDB	İ
-	8	((("MIM" adj capacitor) and channel) and	USPAT;	2003/04/28
		(spacer)) not ((("MIM" adj capacitor) and channel) and (sidewall adj spacer))	US-PGPUB; EPO; JPO;	17:07
			IBM TDB	
	87	(("MIM" adj capacitor) and channel) not	USPĀT;	2003/04/28
Ì		((("MIM" adj capacitor) and channel) and	US-PGPUB;	17:08
1	i	(spacer))	EPO; JPO; IBM TDB	
1 -	86	((("MIM" adj capacitor) and channel) not	USPAT;	2003/04/28
	'	((("MIM" adj capacitor) and channel) and	US-PGPUB;	17:54
	l i	(spacer))) not ((((capacitor adj	EPO; JPO;	
1	ļ.	structure) and leg) and channel) and electrode)	IBM_TDB	İ
-	. 0	20020190279.URPN.	USPAT	2003/04/28
i			i	17:11
-	38	"5700731"	USPAT;	2003/04/28
	i I		US-PGPUB; EPO; JPO;	17:54
			IBM TDB	
'-	6748	(metal adj insulator adj metal) or	USPAT;	2003/04/29
1		(metal-insulator-metal) or "MIM"	US-PGPUB;	09:41
Ī	!		EPO; JPO; IBM TDB	
	26	((metal adj insulator adj metal) or	USPAT;	2003/04/29
		(metal-insulator-metal) or "MIM") and	US-PGPUB;	11:50
		(capacitor and ((lower adj electrode) or	EPO; JPO;	
1		(bottom adj electrode)) and (sidewall adj	IBM_TDB	
1-	4	("5173752" "5330931" "5633781"	USPAT	2003/04/29
		"6344964").PN.		10:06
11 -	33	("4591738" "4954927" "5081559" "5189503" "5192704" "5196909"	USPAT	2003/04/29
Ĩ.		"5208725" "5313089" "5330931"		10:16
1		"5335138" "5365096" "5366920"		
1 1	1	"5371700" "5382817" "5383088"	ĺ	ĺ
		"5384729" "5389566" "5392189"		
i i	'	"5397748" "5401680" "5405796" "5416042" "5436477" "5438011"	i	i
		"5438012" "5442213" "5498889"		
		"5527723" "5573979" "5583360"	:	
1	9000	"5585998" "5631185" "5701647").PN.	uann.	2002 (04 (20
17	3643	capacitor with ((sidewall spacer) or spacer)	USPAT; US-PGPUB;	2003/04/29
1	i i	JP4C61)	EPO; JPO;	11.40
1			IBM_TDB	
-	3624	(capacitor with ((sidewall spacer) or	USPAT;	2003/04/29
1		spacer)) not (((metal adj insulator adj metal) or (metal-insulator-metal) or	US-PGPUB; EPO; JPO;	11:05
1 .	. j	"MIM") and (capacitor and ((lower ad)	: IBM TDB	
1		electrode) or (bottom adj electrode)) and		
	1100	(sidewall adj spacer)))		
-	1128	((capacitor with ((sidewall spacer) or spacer)) not (((metal adj insulator adj	USPAT; US-PGPUB;	2003/04/29
į.	' 1	metal) or (metal-insulator-metal) or	EPO; JPO;	11.00
1 1		"MIM") and (capacitor and ((lower adj	IBM_TDB	T I
]	electrode) or (bottom adj electrode)) and	_	
177		(sidewall adj spacer)))) and channel		I

	264	(((capacitor with ((sidewall spacer) or	USPAT;	2003/04/29
		spacer)) not (((metal adj insulator adj	US-PGPUB;	11:55
		metal) or (metal-insulator-metal) or	EPO; JPO;	
1		"MIM") and (capacitor and ((lower adj	IBM TDB	i
		electrode) or (bottom adj electrode)) and	_	
		(sidewall adj spacer)))) and channel) and		
		((titanium adj nitride) or ("TiN"))		
-	64	((((capacitor with ((sidewall spacer) or	USPAT;	2003/04/29
		spacer)) not (((metal adj insulator adj	US-PGPUB;	11:55
		metal) or (metal-insulator-metal) or	EPO; JPO;	
1		"MIM") and (capacitor and ((lower adj	IBM_TDB	1
		electrode) or (bottom adj electrode)) and	_	
		(sidewall adj spacer)))) and channel) and		
		((titanium adj nitride) or ("TiN"))) and		
		(("Ta.sub.2 O.sub.5" or (tantalum adj		
		pentoxide)))	1	
-	0	(((((capacitor with ((sidewall spacer) or	USPAT;	2003/04/29
		spacer)) not (((metal adj insulator adj	US-PGPUB;	11:08
		metal) or (metal-insulator-metal) or	EPO; JPO;	
		"MIM") and (capacitor and ((lower adj	IBM_TDB	
i i		electrode) or (bottom adj electrode)) and	_	
		(sidewall adj spacer)))) and channel) and		
i		((titanium adj nitride) or ("TiN"))) and		
		(("Ta.sub.2 O.sub.5" or (tantalum adj		
		pentoxide)))) and (ammonia adj plasma)		
- !	47		USPAT;	2003/04/29
		spacer)) not (((metal adj insulator adj	US-PGPUB;	11:09
		metal) or (metal-insulator-metal) or	EPO; JPO;	1
		"MIM") and (capacitor and ((lower adj	IBM_TDB	
		electrode) or (bottom adj electrode)) and		
!		(sidewall adj spacer)))) and channel) and		
		((titanium adj nitride) or ("TiN"))) and		
i i		(("Ta.sub.2 O.sub.5" or (tantalum adj	ł.	
		pentoxide)))) and (plasma)	1	
-	16	(((((capacitor with ((sidewall spacer)	USPAT;	2003/04/29
1		or spacer)) not (((metal adj insulator	US-PGPUB;	11:56
		adj metal) or (metal-insulator-metal) or	EPO; JPO;	
		"MIM") and (capacitor and ((lower adj	IBM_TDB	1
i		electrode) or (bottom adj electrode)) and		
		(sidewall adj spacer)))) and channel) and		
		((titanium adj nitride) or ("TiN"))) and		
		(("Ta.sub.2 O.sub.5" or (tantalum ad)	Ī	1
*		pentoxide)))) and (plasma)) and (ammonia)		
-	2029	(capacitor with ((sidewall spacer) or	USPAT;	2003/04/29
		spacer)) and (conduct\$4 same ((sidewall	US-PGPUB;	11:50
		spacer) or spacer))	EPO; JPO;	į.
			IBM_TDB	
- !	595	((capacitor with ((sidewall spacer) or	IBM_TDB USPAT;	2003/04/29
-	595	((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall	IBM_TDB USPAT; US-PGPUB;	2003/04/29 11:51
-	595	((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer))) and ((lower adj	IBM_TDB USPAT; US-PGPUB; EPO; JPO;	
-		((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer))) and ((lower adj electrode) or (bottom adj electrode))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB	11:51
-	595 271	((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer))) and ((lower adj electrode) or (bottom adj electrode)) (((capacitor with ((sidewall spacer) or	IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB USPAT;	2003/04/29
-		{(capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer))) and ((lower adj electrode) or (bottom adj electrode)) (((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall	IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB USPAT; US-PGPUB;	11:51
-		((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer))) and ((lower adj electrode) or (bottom adj electrode)) (((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer))) and ((lower adj	IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB USPAT; US-PGPUB; EPO; JPO;	2003/04/29
-		((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer))) and ((lower adj electrode) or (bottom adj electrode)) (((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer))) and ((lower adj electrode) or (bottom adj electrode)))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB USPAT; US-PGPUB;	2003/04/29
-	271	((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer)) and ((lower adj electrode) or (bottom adj electrode)) (((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) spacer))) and ((lower adj electrode) or (bottom adj electrode))) and ((tianium adj nitride) or ("TiN"))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB	11:51 2003/04/29 11:55
-	271	((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer)) and ((lower adj electrode) or (bottom adj electrode)) (((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer))) and ((lower adj electrode) or (bottom adj electrode)) and ((titanium adj nitride) or ("TiN")) ((((capacitor with ((sidewall spacer) or spacer))) and (((titanium adj nitride) or ("TiN"))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB USPAT;	11:51 2003/04/29 11:55 2003/04/29
-	271	((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer))) and ((lower adj electrode) or (bottom adj electrode)) (((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer))) and ((lower adj electrode) or (bottom adj electrode)) and ((tianium adj nitride) or ("TiN")) ((((capacitor with ((sidewall spacer) or spacer))) and (conduct\$4 same ((sidewall	IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB USPAT; US-PGPUB;	11:51 2003/04/29 11:55
	271	((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer)) and ((lower adj electrode) or (bottom adj electrode) (((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer)) and (lower adj electrode) or (bottom adj electrode)) and ((titanium adj nitride) or ("TiN")) ((((capacitor with ((sidewall spacer) or spacer))) and ((lower adj electrode))) and ((lower)) and (conduct\$4 same ((sidewall spacer) or spacer)) and (lower adj	IBM TDB USPAT; US-PGPUB; EPO; JPO; IBM TDB USPAT; US-PGPUB; EPO; JPO; IBM TDB USPAT; US-PGPUB; EPO; JPO;	11:51 2003/04/29 11:55 2003/04/29
	271	((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer)) and ((lower adj electrode) or (bottom adj electrode)) (((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer)) and ((lower adj electrode) or (bottom adj electrode)) and ((tianium adj nitride) or ("TiN")) ((((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer)) and ((lower adj electrode)) and (conduct\$4 same ((sidewall spacer) or spacer))) and ((lower adj electrode) or (bottom adj electrode)))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB USPAT; US-PGPUB;	11:51 2003/04/29 11:55 2003/04/29
0.00	271	((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer)) and (clower adj electrode) or spacer)) and (clower adj electrode) or ((capacitor with ((sidewall spacer) or spacer)) and (clower adj electrode)) and (sidewall spacer) or spacer)) and (clower adj) and (clower adj) and (clower adj) and (clower adj)) and (clower adj)) and (clower adj) and (clower adj) and (clower adj) and (clower adj) and (conduct\$4 same ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall adj electrode) or (bottom adj electrode)) and ((titanium adj nitride) or ("TiN"))	IBM TDB USPAT; US-PGPUB; EPO; JPO; IBM TDB USPAT; US-PGPUB; EPO; JPO; IBM TDB USPAT; US-PGPUB; EPO; JPO;	11:51 2003/04/29 11:55 2003/04/29
0 0	271	((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer)) and ((lower adj electrode) or (sold spacer) or (bottom adj electrode)) (((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer)) and (clower adj electrode) or (bottom adj electrode)) and ((lower adj electrode) or (bottom adj electrode)) and (((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer))) and ((lower adj electrode) or (bottom adj electrode)) and ((titanium adj nitride) or ("TiN")) and ((titanium adj nitride) ("tantalum adj and (("Ta.sub.2 O. sub.5" or (tantalum adj	IBM TDB USPAT; US-PGPUB; EPO; JPO; IBM TDB USPAT; US-PGPUB; EPO; JPO; IBM TDB USPAT; US-PGPUB; EPO; JPO;	11:51 2003/04/29 11:55 2003/04/29
0 0 0 1	271 129	((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer)) and ((lower adj electrode) or spacer)) and (clower adj electrode) or ((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer)) and (clower adj electrode) or spacer)) and (clower adj electrode) or spacer) and (pottom adj electrode) or spacer) and (interior or "TiN") and ((conduct\$4 same ((sidewall spacer) and (conduct\$4 same ((sidewall spacer) and (conduct\$4 same ((sidewall spacer) or spacer)) and ((indewind adj electrode) or (bottom adj electrode)) and ((itranium adj nitride) or ("TiN")) and (("Ta.sub.2 O.sub.5" or (tantalum adj pentoxide)))	IBM TDB US-PGPUB; EPO; JPO; IBM TDB US-PGPUB; EPO; JPO; IBM_TDB US-PGPUB; EPO; JPO; IBM_TDB US-PGPUB; EPO; JPO; IBM_TDB	11:51 2003/04/29 11:55 2003/04/29 11:55
00 000	271	((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer)) and ((lower adj electrode) or (bottom adj electrode)) (((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or adj electrode)) and ((tower adj electrode) or (bottom adj electrode)) and ((idewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer)) and ((lower adj electrode) or (bottom adj electrode)) and ((sidewall spacer) or spacer)) and ((lower adj electrode)) and ((sidemall spacer) or spacer)) and ((titanium adj nitride) or ("TiN")) and ((fitanium adj nitride) or ("tantalum adj pentoxide))) (((((capacitor with ((sidewall spacer) or	IBM TDB USPAT; US-PGPUB; EPO; JPO; IBM TDB US-PAT; US-PGPUB; EPO; JPO; IBM TDB USPAT; US-PGPUB; EPO; JPO; IBM TDB USPAT; US-PGPUB; US-PGPUB; US-PGPUB; US-PGPUB; US-PGPUB;	2003/04/29 11:55 2003/04/29 11:55
0.00	271 129	((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer)) and (clower adj electrode) or spacer)) and ((lower adj electrode)) (((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer)) and ((lower adj electrode)) and ((lower adj electrode)) and ((idewall spacer)) and (idewall spacer)) and ((idewall spacer)) and (idewall spacer)) and (idewall spacer) and (conduct\$4 same ((sidewall spacer))	IBM TDB USPAT; US-PGPUB; EPO; JPO; IBM TDB US-PGPUB; EPO; JPO; IBM_TDB US-PGPUB; EPO; JPO; IBM_TDB US-PGPUB; EPO; JPO; IBM_TDB US-PGPUB; US-PGPUB; US-PGPUB; US-PGPUB;	11:51 2003/04/29 11:55 2003/04/29 11:55
	271 129	((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer)) and ((lower adj electrode) or (bottom adj electrode)) (((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or adj electrode)) and ((titenium adj nitride) or ("TiN")) ((((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer)) and ((lower adj electrode) or (bottom adj electrode)) and ((itanium adj nitride) or ("TiN")) and ((itanium adj nitride) or (sidewall spacer)) and (conduct\$4 same ((sidewall spacer)) and (conduct\$4 same ((sidewall spacer)) or spacer)) and ((lower adj	IBM TDB USPĀT; US-PGPUB; EPO; JPO; IBM TDB US-PGPUB; EPO; JPO; IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/29 11:55 2003/04/29 11:55
000	271 129	((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer))) and ((lower adj electrode) or spacer))) and ((lower adj electrode)) (((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer)) and (conduct\$4 same ((sidewall spacer))) and ((lower adj electrode)) and ((indewal adj electrode)) and ((indewall spacer) or spacer)) and ((indewall spacer) or spacer))) and ((lower adj spacer) or spacer))) and ((lower adj)) and (("Tanium adj nitride) or ("TiN")) and (("Tanium adj nitride) or ("TiN")) and (("Ta.sub.2 0.sub.5" or [tantalum adj pentoxide))) {((((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer))) and ((lower adj electrode) or (bettom adj electrode))	IBM TDB USPAT; US-PGPUB; EPO; JPO; IBM TDB US-PGPUB; EPO; JPO; IBM_TDB US-PGPUB; EPO; JPO; IBM_TDB US-PGPUB; EPO; JPO; IBM_TDB US-PGPUB; US-PGPUB; US-PGPUB; US-PGPUB;	2003/04/29 11:55 2003/04/29 11:55
	271 129	((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer)) and ((lower adj electrode) or (bottom adj electrode)) (((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or adj electrode) or (bottom adj electrode)) and ((citanium adj nitride) or ("TiN")) ((((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer)) and ((lower adj electrode) or (bottom adj electrode)) and ((titanium adj nitride) or ("TiN")) and (((titanium adj nitride) or ("TiN")) and ((((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer)) and (or spacer)) and ((lower adj electrode)) or (bottom adj electrode)) and ((titanium adj nitride) or ("TiN")))	IBM TDB USPĀT; US-PGPUB; EPO; JPO; IBM TDB US-PGPUB; EPO; JPO; IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/29 11:55 2003/04/29 11:55
0.000	271 129	((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer))) and ((lower adj electrode) or spacer))) and ((lower adj electrode)) (((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer)) and (conduct\$4 same ((sidewall spacer))) and ((lower adj electrode)) and ((indewal adj electrode)) and ((indewall spacer) or spacer)) and ((indewall spacer) or spacer))) and ((lower adj spacer) or spacer))) and ((lower adj)) and (("Tanium adj nitride) or ("TiN")) and (("Tanium adj nitride) or ("TiN")) and (("Ta.sub.2 0.sub.5" or [tantalum adj pentoxide))) {((((capacitor with ((sidewall spacer) or spacer)) and (conduct\$4 same ((sidewall spacer) or spacer))) and ((lower adj electrode) or (bettom adj electrode))	IBM TDB USPĀT; US-PGPUB; EPO; JPO; IBM TDB US-PGPUB; EPO; JPO; IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/29 11:55 2003/04/29 11:55

-	79	(((((capacitor with ((sidewall spacer)	USPAT;	2003/04/29
		or spacer)) and (conduct\$4 same	US-PGPUB;	11:56
T.		((sidewall spacer) or spacer))) and	EPO; JPO;	11.00
		((lower adj electrode) or (bottom adj	IBM TDB	
		electrode))) and ((titanium adj nitride)	IBM_IDB	
i		erectrode// / and ((treamrum adj hitride)		
1		or ("TiN"))) and (("Ta.sub.2 O.sub.5" or	1	
		(tantalum adj pentoxide)))) and plasma)		
i i		not ((((((capacitor with ((sidewall		1
		spacer) or spacer)) not (((metal adj		
		insulator adj metal) or	!	
		(metal-insulator-metal) or "MIM") and	1	
		(capacitor and ((lower adj electrode) or		4
1		(bottom adj electrode)) and (sidewall adj		
1		spacer)))) and channel) and ((titanium	ļ	1
		adi mitride) on ("TiN"))) and ((CICANITUM)	1	
1		adj nitride) or ("TiN"))) and (("Ta.sub.2		4
		O.sub.5" or (tantalum adj pentoxide))))		
		and (plasma)) and (ammonia))		
-	48	(((((capacitor with ((sidewall spacer) or	; USPAT;	2003/04/29
j		spacer)) not (((metal adj insulator adj	US-PGPUB;	11:58
		metal) or (metal-insulator-metal) or	EPO; JPO;	1
		"MIM") and (capacitor and ((lower ad)	IBM TDB	1
			1011_100	
i		electrode) or (bottom adj electrode)) and		1
į		(sidewall adj spacer)))) and channel) and		
		((titanium adj nitride) or ("TiN"))) and	i .	1
		(("Ta.sub.2 O.sub.5" or (tantalum adj	İ	
		pentoxide)))) not ((((((capacitor with		
i		((sidewall spacer) or spacer)) not		1
		(((metal adj insulator adj metal) or	1	1
		(metal-insulator-metal) or "MIM") and		i
		(capacitor and ((lower adj electrode) or	1	
i		(bottom adj electrode)) and (sidewall adj		
		spacer)))) and channel) and ((titanium	1	
		adj nitride) or ("TiN"))) and (("Ta.sub.2		
!		O.sub.5" or (tantalum adj pentoxide))))		j
		and (plasma)) and (ammonia))		1
. 1	111	((((((capacitor with ((sidewall spacer)	USPAT;	2003/04/29
	111			14:46
		or spacer)) and (conduct\$4 same	US-PGPUB;	14:46
		((sidewall spacer) or spacer))) and	EPO; JPO;	
		((lower adj electrode) or (bottom adj	IBM_TDB	
		electrode))) and ((titanium adj nitride)		1
		or ("TiN"))) and (("Ta.sub.2 O.sub.5" or		1
		(tantalum adj pentoxide)))) and plasma)		İ
		not ((((((capacitor with ((sidewall	!	
i		spacer) or spacer)) not (((metal adj		
			İ	ļ.
		insulator adj metal) or		
		(metal-insulator-metal) or "MIM") and		1
1		(capacitor and ((lower adj electrode) or	:	
		(bottom adj electrode)) and (sidewall adj	1	
		spacer)))) and channel) and ((titanium	1	
!		adj nitride) or ("TiN"))) and (("Ta.sub.2		
		O.sub.5" or (tantalum adj pentoxide))))		1
		and (plasma)) and (ammonia))) or		
!		(((((capacitor with ((sidewall spacer)	I .	
		or spacer)) not (((metal adj insulator	1	
		adj metal) or (metal-insulator-metal) or	1	1
		"MIM") and (capacitor and ((lower ad)	1	1
		electrode) or (bottom adj electrode)) and	•	
		(sidewall adj spacer)))) and channel) and	1	
1		((titanium adj nitride) or ("TiN"))) and		1
		(("Ta.sub.2 O.sub.5" or (tantalum adj	1	7
		pentoxide)))) not ((((((capacitor with		1
1		((sidewall spacer) or spacer)) not		1
		(((metal adj insulator adj metal) or		1
Ĭ		(motel-inculator metal) or "MTM")	1	
		(metal-insulator-metal) or "MIM") and		
		(capacitor and ((lower adj electrode) or	1	1
		(bottom adj electrode)) and (sidewall adj		
	N.	(bottom adj electrode)) and (sidewall adj spacer)))) and channel) and ((titanium		
		spacer)))) and channel) and ((titanium		I
		<pre>spacer)))) and channel) and ((titanium adj nitride) or ("TiN"))) and (("Ta.sub.2</pre>		
		spacer)))) and channel) and ((titanium		

	111	((((((((capacitor with ((sidewall spacer)	USPAT;	2003/04/29
		or spacer)) and (conduct\$4 same	US-PGPUB;	11:59
!		((sidewall spacer) or spacer))) and	EPO; JPO;	i
i		((lower adj electrode) or (bottom adj	IBM_TDB	
		electrode))) and ((titanium adj nitride)	. –	1
	į i	or ("TiN"))) and (("Ta.sub.2 O.sub.5" or	Į.	
		(tantalum adj pentoxide)))) and plasma)		
	!	not ((((((capacitor with ((sidewall		
i i	i	spacer) or spacer)) not ((metal adj		
		insulator adj metal) or		
		(metal-insulator-metal) or "MIM") and		
		(capacitor and ((lower adj electrode) or	l	İ
		(bottom adj electrode)) and (sidewall adj spacer)))) and channel) and ((titanium	\	
		adj nitride) or ("TiN"))) and (("Ta.sub.2		
1	1	O.sub.5" or (tantalum adj pentoxide))))	İ	
		and (plasma)) and (ammonia))) or		
		((((((capacitor with ((sidewall spacer)		
1		or spacer)) not (((metal adj insulator	1	
I I		adj metal) or (metal-insulator-metal) or		İ
i 1		"MIM") and (capacitor and ((lower ad)	1	1
	1	electrode) or (bottom adj electrode)) and		
'	1	(sidewall adj spacer)))) and channel) and		
. 1		((titanium adj nitride) or ("TiN"))) and	i	
		(("Ta.sub.2 O.sub.5" or (tantalum adj		
		pentoxide)))) not ((((((capacitor with		ļ
1	i	((sidewall spacer) or spacer)) not		
i ì	l i	(((metal adj insulator adj metal) or (metal-insulator-metal) or "MIM") and	1	
		(capacitor and ((lower ad) electrode) or	i	
		(bottom ad) electrode)) and (sidewall ad)		i
i l		spacer)))) and channel) and ((titanium		
J		adj nitride) or ("TiN"))) and (("Ta.sub.2		
		O.sub.5" or (tantalum adj pentoxide))))	1	1
: 1		and (plasma)) and (ammonia)))) and	l .	l .
		electrode		
-	3643	(capacitor with ((sidewall spacer) or	USPAT;	2003/04/29
	1	spacer))	US-PGPUB;	14:47
i l			EPO; JPO;	1
			IBM_TDB	
1-	2029	((capacitor with ((sidewall spacer) or	USPAT; US-PGPUB;	2003/04/29
i l		spacer)) } and (conduct\$4 same ((sidewall	EPO; JPO;	19.95
		spacer) or spacer))	IBM TDB	
	595	(((capacitor with ((sidewall spacer) or	USPAT;	2003/04/29
1	3,33	spacer))) and (conduct\$4 same ((sidewall	US-PGPUB;	14:50
		spacer) or spacer))) and ((lower adj	EPO; JPO;	
		electrode) or (bottom adj electrode))	IBM TDB	
-	271	((((capacitor with ((sidewall spacer) or	USPAT;	2003/04/29
1		spacer))) and (conduct\$4 same ((sidewall	US-PGPUB;	14:51
i 1		spacer) or spacer))) and ((lower adj	EPO; JPO;	Į.
		electrode) or (bottom adj electrode)))	IBM_TDB	
1		and ((titanium adj nitride) or ("TiN"))		
-	91	(((((capacitor with ((sidewall spacer) or	USPAT;	2003/04/29
		spacer))) and (conduct\$4 same ((sidewall	US-PGPUB;	17:02
		spacer) or spacer))) and ((lower adj	EPO; JPO;	
		electrode) or (bottom adj electrode)))	IBM_TDB	
!		and ((titanium adj nitride) or ("TiN"))) and (("Ta.sub.2 O.sub.5" or (tantalum adj	Ī	ê l
1		pentoxide)) and plasma)	Ĭ.	
- Î	29	("4251326" "4952904" "4985718"	USPAT	2003/04/29
1		"5005102" "5046043" "5109357"	1	15:30
		"5142437" "5142438" "5146299"		
		"5155573" "5164808" "5185689"	1	
		"5191510" "5196909" "5196912"	1	
1				
		"5237188" "5254217" "5257238"	ļ	
		"5237188" "5254217" "5257238" "5258093" "5283462" "5300799"		1
 		"5237188" "5254217" "5257238" "5258093" "5283462" "5300799" "5313089" "5313090" "5329486"		
ļ 		"5237188" "5254217" "5257238" "5258093" "5283462" "5300799"		

	39	"5895239" 	USPAT; US-PGPUB;	2003/04/29 17:02
-	1	("5895239").PN.	EPO; JPO; IBM_TDB USPAT; US-PGPUB;	2003/04/29 17:02
-	0	michael-charles-olewine.in.	EPO; JPO; IBM_TDB USPAT; US-PGPUB;	2003/08/07 17:12
-	0	charles-olewine-michael.in.	EPO; JPO; IBM_TDB USPAT; US-PGPUB;	2003/08/07 17:12
-	0	Olewine-charles-michael.in.	EPO; JPO; IBM_TDB USPAT; US-PGPUB;	2003/08/07 17:13
-	1	Olewine-michael-\$.in.	EPO; JPO; IBM_TDB USPAT; US-PGPUB; EPO; JPO;	2003/08/07 17:13
-	0	20030067023.URPN.	IBM_TDB USPAT	2003/08/07
	13	(("5895239") or ("5700731") or ("5926359") or ("596394") or ("5926359") or ("6177305") or ("6180976") or ("62300629") or ("6232197") or ("62381964") or ("6251740") or ("6252128") or	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/07 17:13
-	8	("589359")).PN. (("58935239") or ("5700731") or (("6479850") or ("5696394") or ("5926359") or ("6177305") or ("6180976") or	USPAT; US-PGPUB; EPO; JPO;	2003/08/07 17:14
	8	("6200629") or ("6232197") or ("6238964") or ("6251740") or ("6259128") or ("583359")).PN.) and plasma (((("5595239") or ("5700731") or	IBM_TDB	2003/08/07
		["6479850") or ("5696394") or ("5926359") or ("6177305") or ("6180976") or ("6200629") or ("6232197") or ("6238964") or ("6251740") or ("6259128") or ("5583359")).PN.) and plasma) and	US-PGPUB; EPO; JPO; IBM_TDB	17:14
Ţ-	0	capacitor ((((("5895239") or ("5700731") or ("6479950") or ("5696394") or ("5926359") or ("6177305") or ("6180976") or ("6200629") or ("6232197") or ("6238964")	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/08/07 17:15
1-	0	(6230229) or (623297) or (6230904) or (6251740") or (6259128") or (75583359")).PN.) and plasma) and capacitor) and (amonias3 or NH\$2) ((((("5895239") or ("5700731") or	USPAT;	2003/08/07
		("6479850") or ("5696394") or ("5926359") or ("6177305") or ("6180976") or ("6200629") or ("6232197") or ("6238964") or ("6251740") or ("6259128") or	US-PGPUB; EPO; JPO; IBM_TDB	17:15
<u> </u>	2	["5583359")).PN.) and plasma] and capacitor) and (annonias3 or NH82) (((("5585239") or ("5700731") or ("6479850") or ("617305") or ("6187305") or ("6187305") or ("6200629") or ("6230869") or ("6206629") or ("6230869")	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/08/07
		or ("6251740") or ("6259128") or ("6251740") or ("6259128") or ("5583359")).PN.) and plasma) and capacitor) and (ammonia\$3 or NH\$2) "6479850"	USPAT;	2003/08/07
		0417000	US-PGPUB; EPO; JPO; IBM_TDB	17:18

_		32	"5583359"	USPAT;	T2003/08/07
î				US-PGPUB;	17:52
		- 1		EPO; JPO;	2.11
				IBM TDB	
-	1	0	kevin-saiz-f.in.	USPAT:	2003/08/07
1		.		US-PGPUB;	17:53
ï		-		EPO; JPO;	17.55
	i i			IBM TDB	
i -		0	kevin-saiz-\$.in.	USPĀT:	2003/08/07
	100	i	NEVIN SAIZ-V.III.	US-PGPUB;	17:53
		1			17.55
1		i		EPO; JPO;	
		,	saiz-kevin-S.in.	IBM_TDB	
		1 1	saiz-kevin-\$.in.	USPAT;	2003/08/07
	ì			US-PGPUB;	17:53
	1	1		EPO; JPO;	1
1	1.0	. 1	and the second s	IBM_TDB	1
-		0	Olewine-Michael-C.in.	USPAT;	2003/08/27
				US-PGPUB;	11:12
				EPO; JPO;	1
,	1	- 1		IBM TDB	
-	1	1	Olewine-Michael-\$.in.	USPAT;	2003/08/27
l.		1		US-PGPUB;	11:13
	i	- 1		EPO: JPO:	1
				IBM TDB	
· -	i	1	saiz-kevin-F.in.	USPAT:	2003/08/27
1		- 1		US-PGPUB;	11:13
	'			EPO; JPO;	1
	i	- 1		IBM TDB	1
1 -	1 7	71	capacitor and (conduct\$4 adj sidewall adj	USPĀT;	2003/08/27
1	1	- 1	spacer)	US-PGPUB;	11:14
		i	Space1)	EPO; JPO;	111.14
		- 1		IBM TDB	
		0 1	(capacitor and (conduct\$4 adj sidewall	USPAT:	2003/08/27
1	- 4	. 0	adj spacer)) and (parallel)	US-PGPUB;	111:14
1		- 1	adj Spacer)) and (parallel)		11:14
1		i		EPO; JPO;	
4				IBM_TDB	
1 -	1	13	((capacitor and (conduct\$4 adj sidewall	USPAT;	2003/08/27
			adj spacer)) and (parallel)) and	US-PGPUB;	11:19
	!		((titanium adj nitride) or "TiN")	EPO; JPO;	
İ	1 .	. i		IBM_TDB	1
1 -	3	32	"5583359"	USPAT;	2003/08/27
1	i	i			11:42
ļ				EPO; JPO;	1
	1	- 4		IBM_TDB	I i
-		2	(("5939766") or ("6385033")).PN.	USPAT;	2003/08/27
	!	- 1		US-PGPUB;	11:50
1	I	i		EPO; JPO;	1
1	1			IBM TDB	
1 -		1 :	("6,177,305").PN.	USPAT;	2003/08/27
1	1	- 1		US-PGPUB;	11:50
1	1	- 1		EPO; JPO;	i i
				IBM TDB	